

# Bruce 2 - Tube 6

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## Facts

Tube 6 is used for the wet oxidation of silicon dioxide.

- Uses hydrogen gas and oxygen to produce a steam for the faster growth of silicon dioxide.
- Wafers are loaded into quartz boats - current sizes include 75mm, 100mm & 150mm.
- Maximum oxide growth is kept to <2um.
- Clean wafers only - no previous metal processing

## Other Tubes

- Bruce Tube 1 - Wet Oxide Growth
- Bruce Tube 2 - P type diffusion
- Bruce Tube 3 - N type diffusion
- Bruce Tube 4 - Dry Oxide Growth
- Bruce Tube 5 - External Torch Low Temp Oxide Growth
- Bruce Tube 6 - Wet Oxide Growth
- Bruce Tube 7 - Anneal
- Bruce Tube 8 - High Temp Anneal

## Personnel

- Tool Engineer -
- Process Engineer - Sean O'Brien
- Process Engineer - Patricia Meller

## Tool & Process Information

- Bruce Furnace Recipe Request Sheet
  - If a new recipe is needed for the Bruce Furnace, fill out this sheet and return to Sean O'Brien

## Manuals & Users

- Bruce Furnace Manual
- Bruce Furnace Certification Checklist